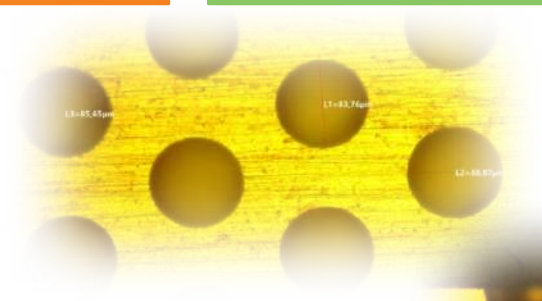
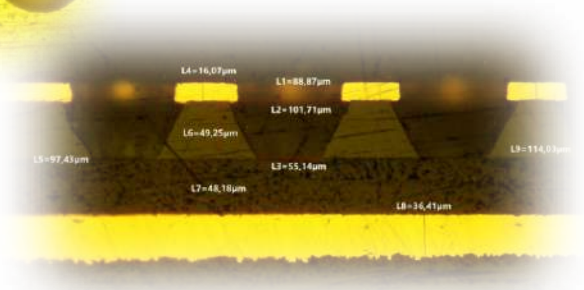
AIDAinnova-WP7.3.2

Industrial engineering of high rate μ-RWELL





Matteo Giovannetti [LNF-INFN]

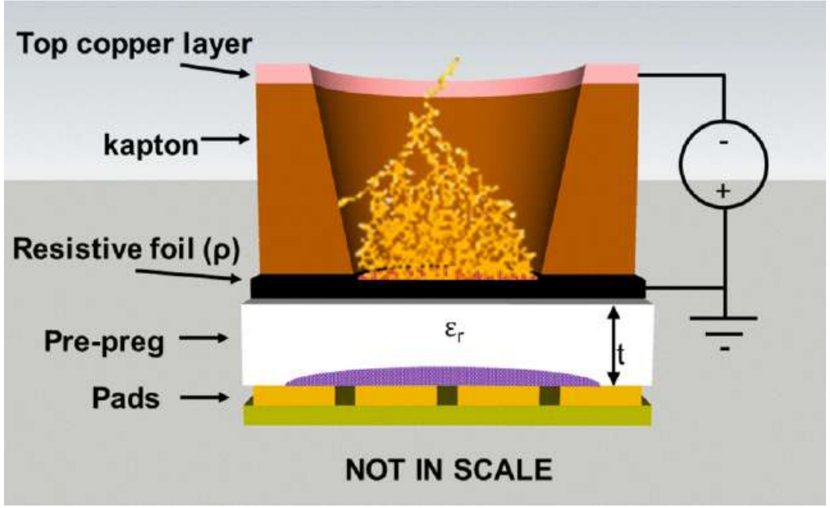
on behalf of
LNF-INFN (leading group)
Bologna-Ferrara INFN teams
R. De Oliveira – CERN-EP-DT-MPT Workshop
R. Pinamonti, M. Pinamonti – ELTOS S.p.A.

INFN LNF - DDG

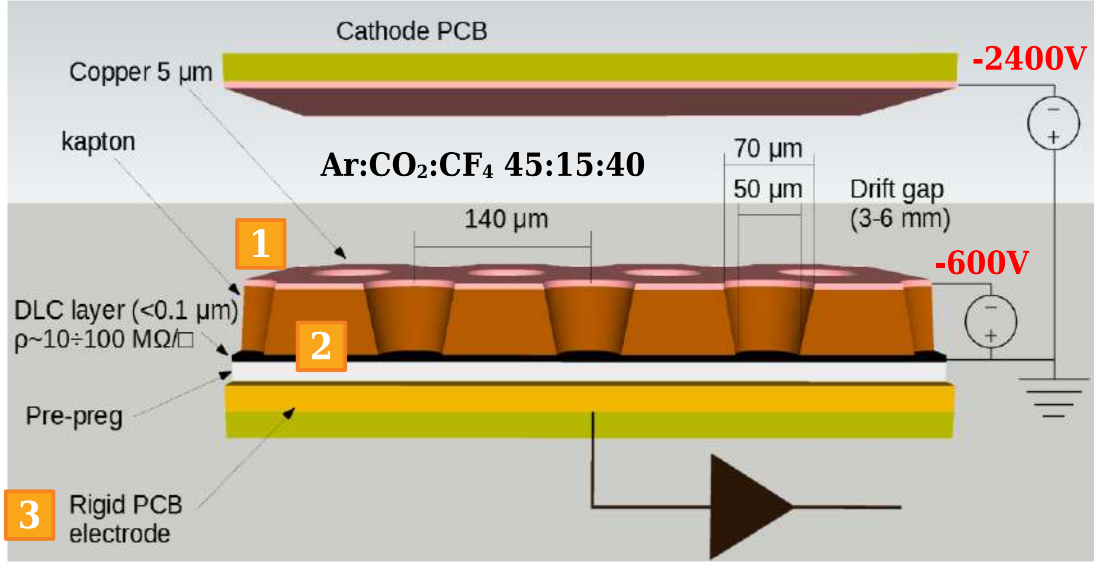
AIDAinnova 2nd annual meeting, Valencia, April 24th-27th 2023

The μ-RWELL detector (reminder)

The μ-RWELL is a Micro Pattern Gaseous Detector (MPGD) composed of only two elements: the μ-RWELL_PCB and the cathode. **The core is the μ-RWELL_PCB**, realized by coupling three different elements:



Applying a suitable voltage between the **top Cu-layer and the DLC** the WELL acts as a **multiplication channel for the ionization** produced in the conversion/drift gas gap.



1. a **WELL** patterned kapton foil acting as **amplification stage** (GEM-like)
2. a **resistive DLC layer (Diamond-Like-Carbon)** for discharge suppression with surface resistivity ~ 50÷100 MΩ/□
3. a standard readout PCB

Task objectives

DELIVERABLE - m30

- **D7.3:** μ-RWELL prototypes co-produced by industry under the guidance and supervision of the research team. A complete report will be provided (Task 7.3)

MILESTONE - m36

- **MS27:** build a $0.3\times0.3\ m^2$ prototype and the readout plane, with the new structure

Operative Meetings

21st Sept. 2021 - joint INFN-ELTOS-CERN meeting

- standardizing manufacturing procedures of µ-RWELL layout

1st-3rd Dec. 2021 - CERN-INFN meeting

- status of the R&D on the High Rate layout
- 2D layout based on the readout of a segmented amplification stage

7th–10th Dec. 2021 – 1st test batch in ELTOS

- DLC patterning
- PCB planarizing tests

7th–8th Mar. 2022 - 2nd test batch in ELTOS

- PCB planarizing tests
- Kapton DLCed foil coupling with PCB-readout

28th-31th Mar. 2022
1st AIDAinnova
Annual meeting

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1st AIDAinnova
Annual meeting

31st Oct. 2022 - joint INFN-CERN meeting
- Discussion with Rui about the results obtained
- Planning 2023 production

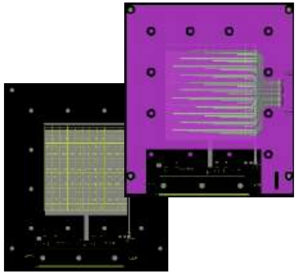
5th Dec. 2022 - joint INFN-ELTOS meeting
- Planning 2023 production

20th-22th Mar. 2023 - 1st production batch in ELTOS
- DLC patterning
- PCB palnarizing (prepreg thickness scan)

24th-27th Apr. 2023
2nd AIDAinnova
Annual meeting

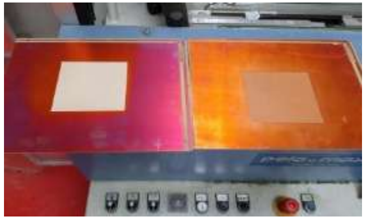
WP7.3.2: Technology Transfer (flow chart)

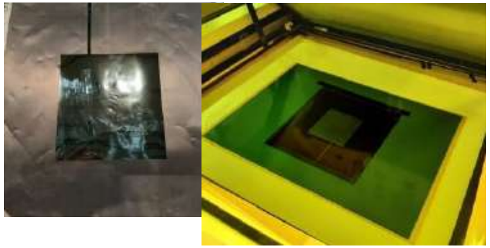
LAYOUT design



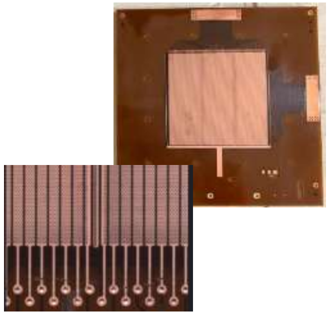
Feedback from tests

PCB production





Final detector manufacturing



DCL foil production (*)

*DLC Magnetron Sputtering machine co-funded by INFN- CSN1

WP7.3.2: Technology Transfer 2022

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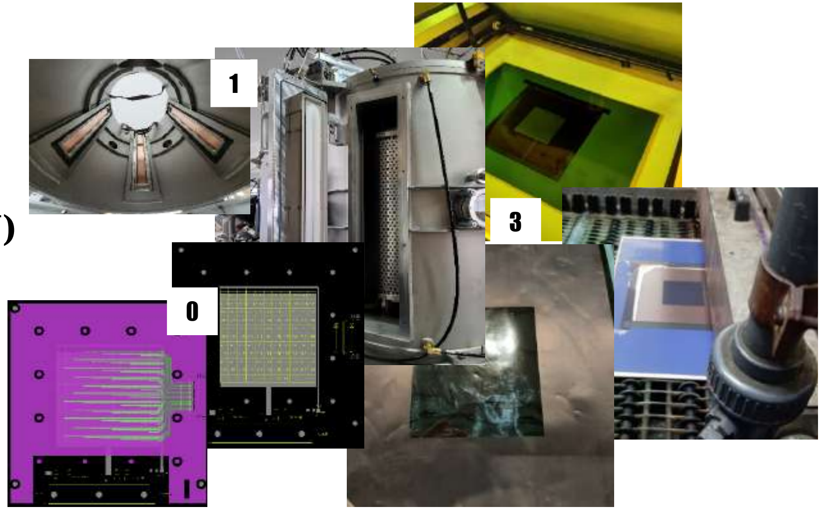
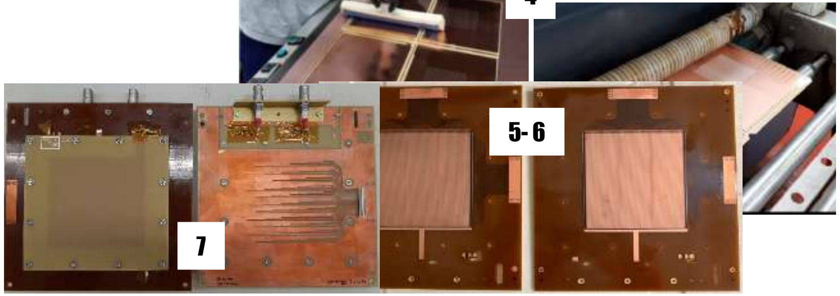
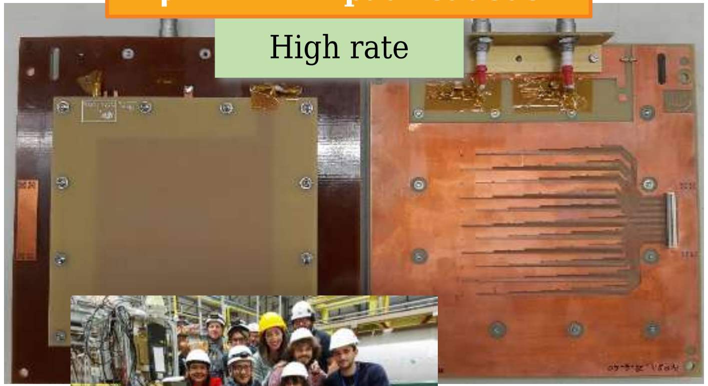


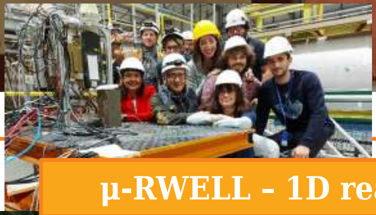


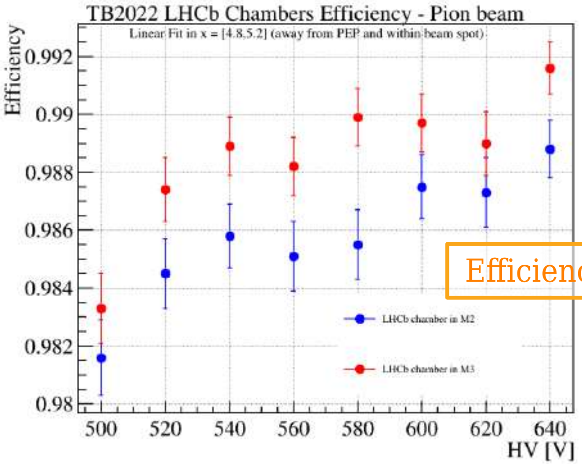
WP7.3.2: μ-RWELL layouts co-built by ELTOS & CERN (Oct.'22)

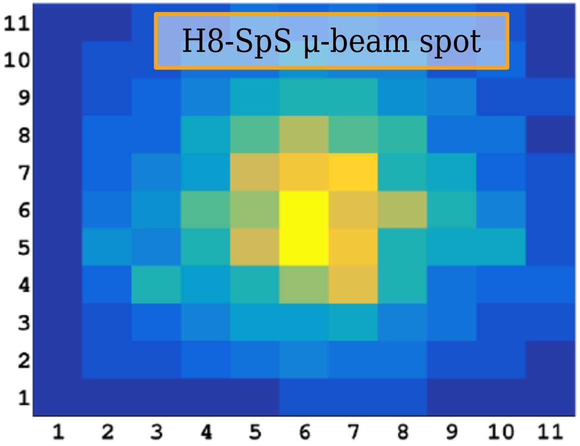
μ-RWELL – pad readout

High rate



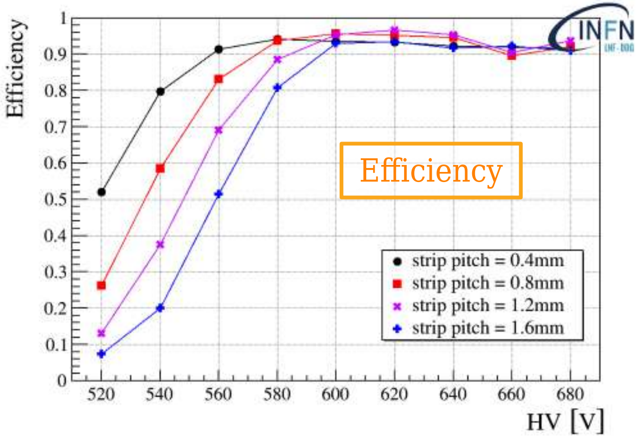


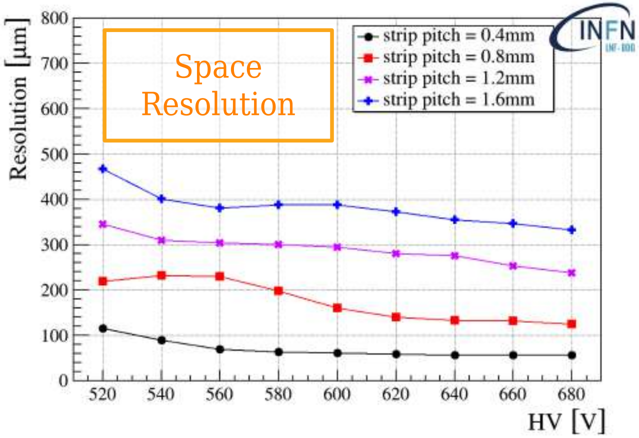




μ-RWELL – 1D readout

Tracking





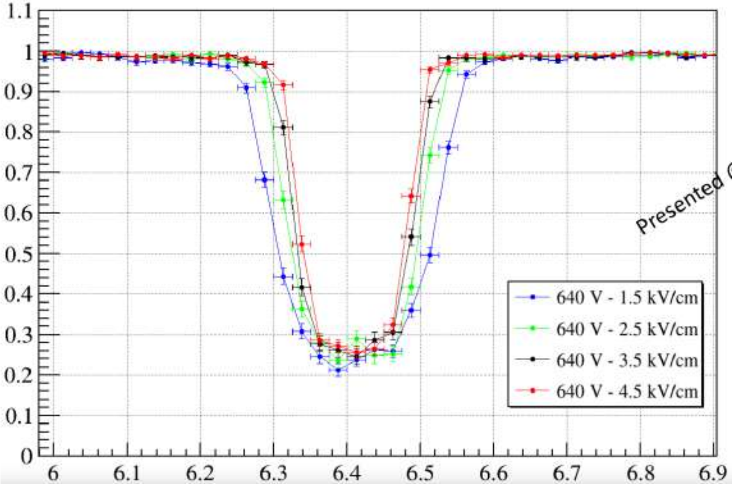
WP7.3.2: (June '23) PEP optimization

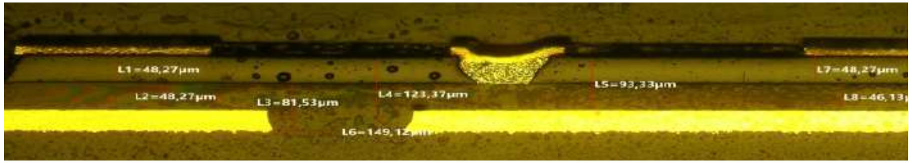
2022

PEP µ-RWELL:
DLC grounding by conductive groove

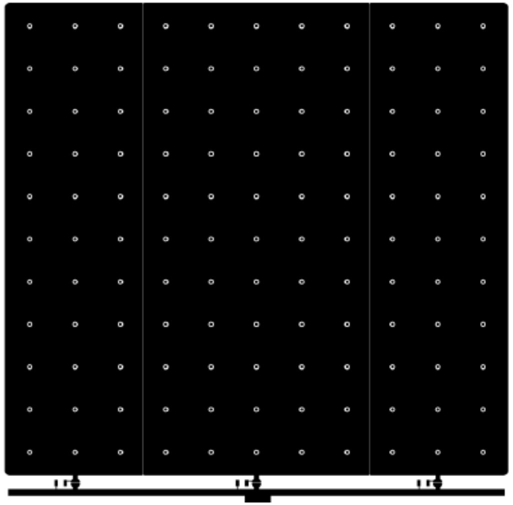
Pad R/O = 9×9cm^2
Grounding:
- pitch = 9mm
- width = 1.5mm

→ 84% geometric acceptance

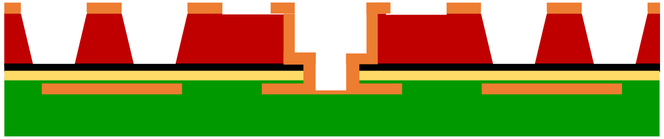




2023

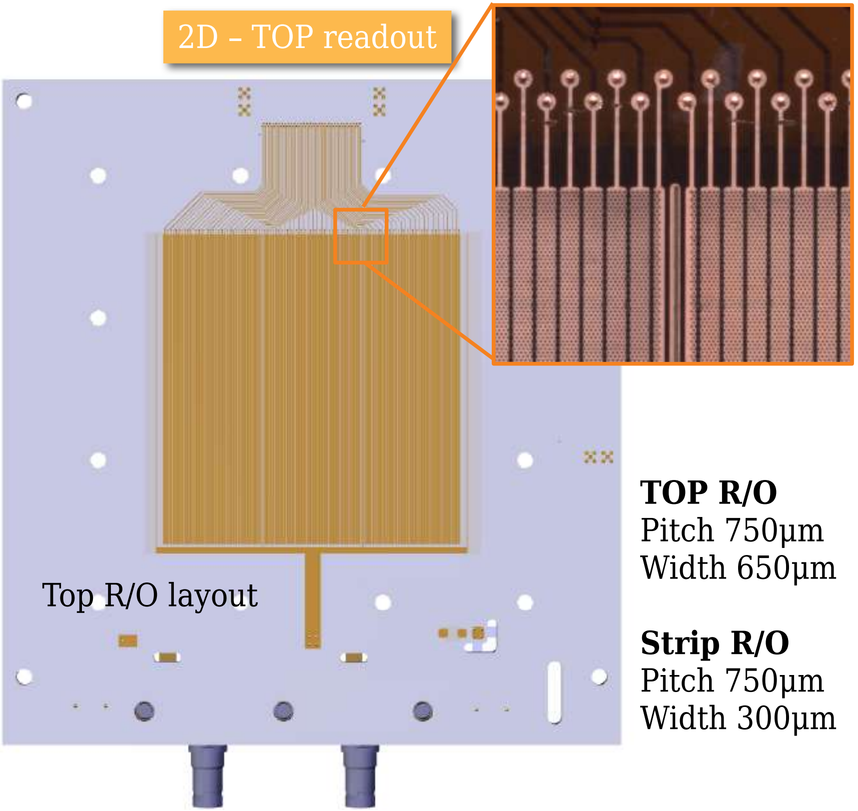


PEP-dot µ-RWELL:
DLC grounding by conductive dot connected to the readout
Dot rim = 1.6mm | Pad R/O = 9×9cm^2
→ 97% geometric acceptance



WP7.3.2: (June '23) 2D Read Out

2D – TOP readout



TOP R/O
Pitch 750μm
Width 650μm

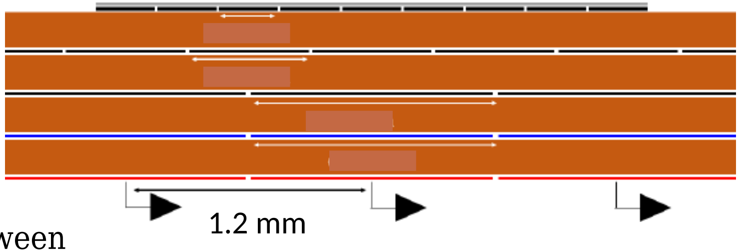
Strip R/O
Pitch 750μm
Width 300μm

No PEP in the active area
Kapton foil between DLC and strip R/O:
stacking 25+12+25μm (pre-preg/kapton/pre-preg)
ρ_S= 20 MΩ/□

2D – capacitive sharing

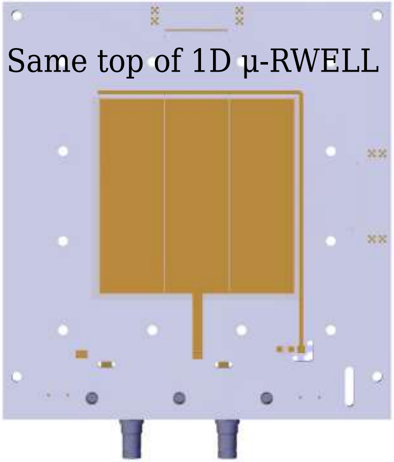
Inspired by another
μ-RWELL R&D:
K. Gnanvo et al., NIM A
1047 (2023) 167782

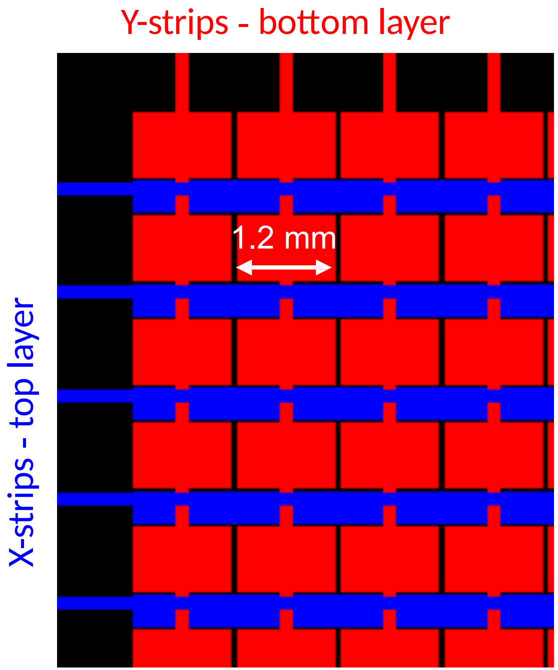
Trasversal view



Capacitive coupling between
TOP and R/O:
3 layers of pads (L=0.3/0.6/1.2mm)

No PEP in the active area
ρ_S= 60 MΩ/□





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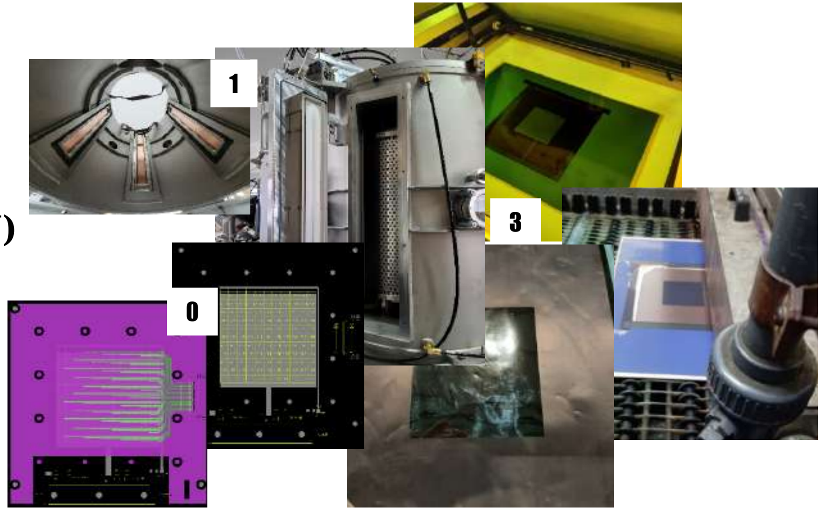

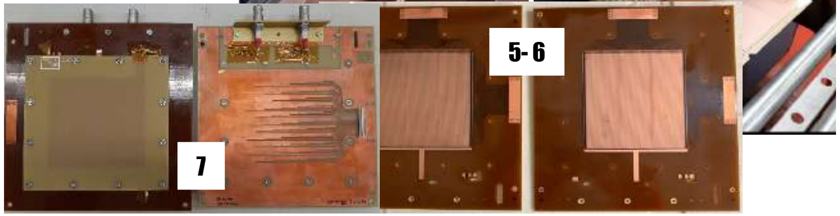

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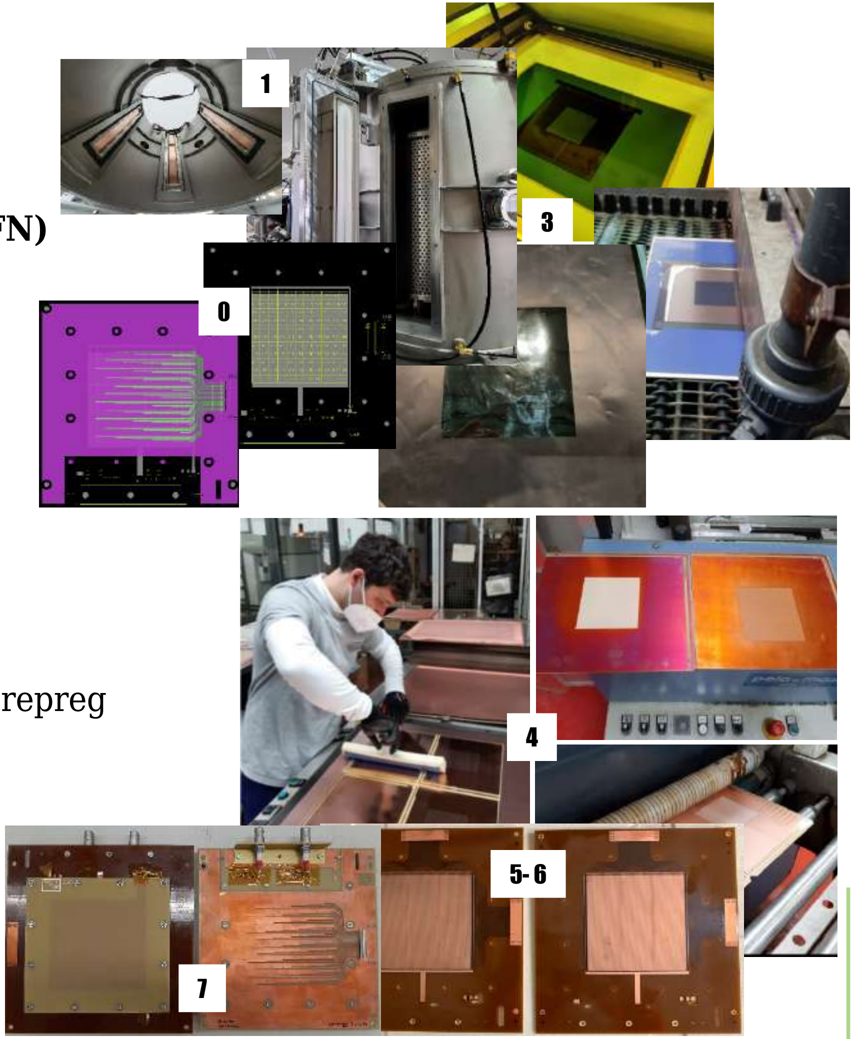


WP7.3.2: update on the CERN-INFN DLC machine

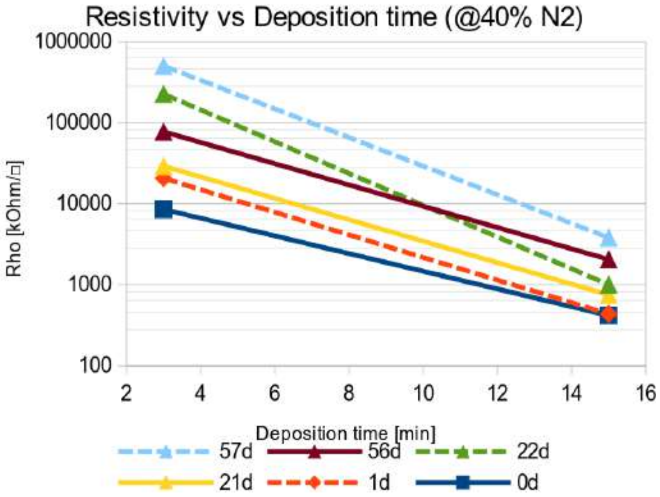
31st Oct. 2022 – Delivered
31st Oct. - 4th Nov. 2022 – Commissioning & test training
21st - 23rd Nov. 2022 – First DLC sputtering test
- Ar + N_2 doping

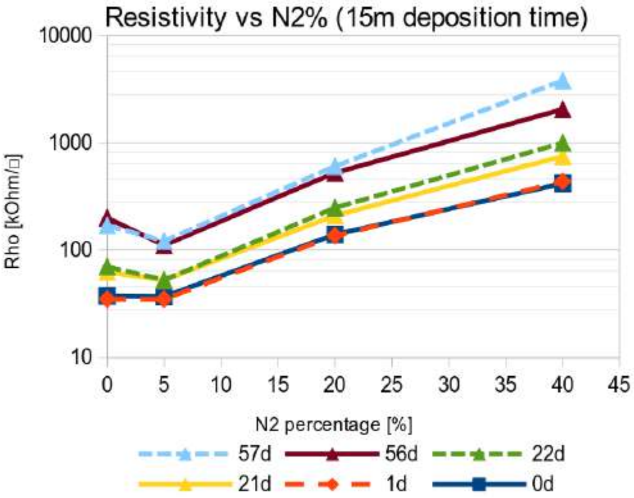
5th - 9th Jun. 2023 – Second DLC sputtering test
- Ar + C_2H_2 doping

Some technical features:
- **Flexible** substrates up to 1.7m×0.6m
- **Rigid** substrates up to 0.2m×0.6m

Five cooled target holders, arranged as two pairs face to face and one on the front, equipped with five shutters.

The machine shall be able to **sputter or co-sputter different materials,** in order to create a coating layer by layer or an adjustable gradient in the coating.





WP7.3.2: Mar.’23 ELTOS production – DLC patterning

Step 2:

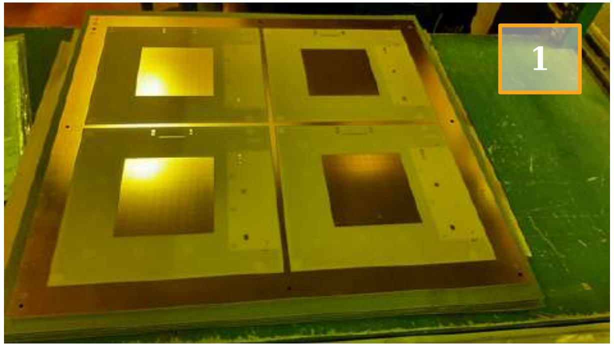
1) **PCB** production

<u>Step 3:</u>

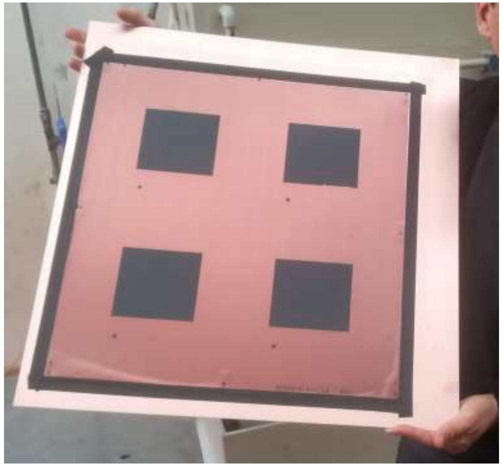
2) Photoresist **lamination** for DLC protection

3) Photoresist **development**

4) **DLC patterning** with brushing machine (@CERN different approach: JET-SCRUBBING)



DLC
Kapton
Cu



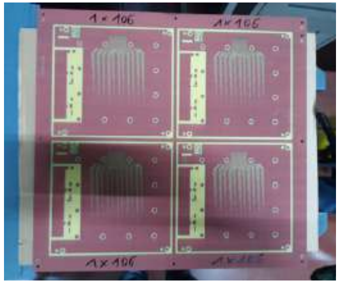
WP7.3.2: Mar.'23 ELTOS production – DLC-foil gluing

<u>Step 4:</u> Cu-Kapton-DLC gluing on PCB

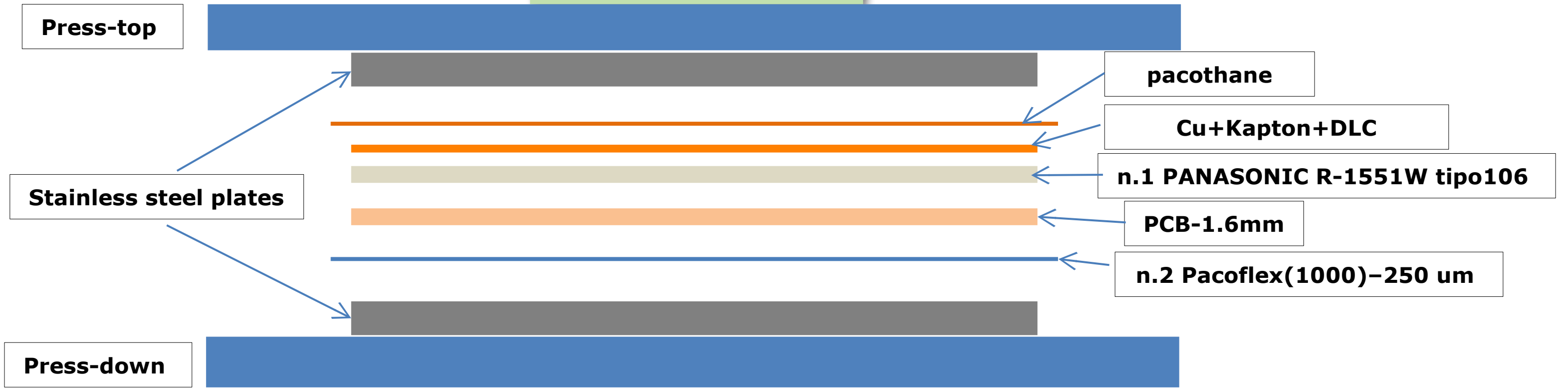
Goal: 16 PEP-dot detectors (9×9mm^2 pad R/O),
with **different pre-preg thickness:**
systematic study of signal **pulse width as a function of coupling capacitance** between DLC and R/O pad.

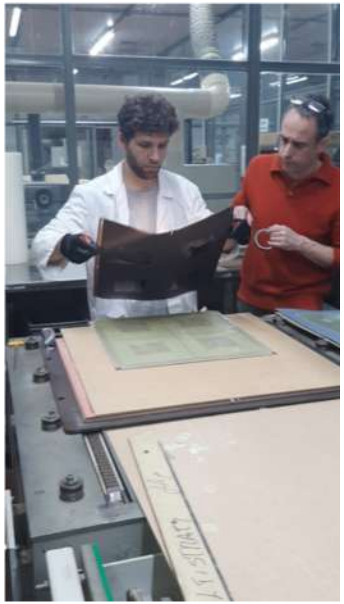
Waiting for shipment to CERN and detector finalization (Step 5-7)

Pre-preg	Δx [µm]
106	50
1080	75
x2 106	100
x2 1080	150



Main parameters:
Pressure 180 N/cm^2
Temperature 210 °C



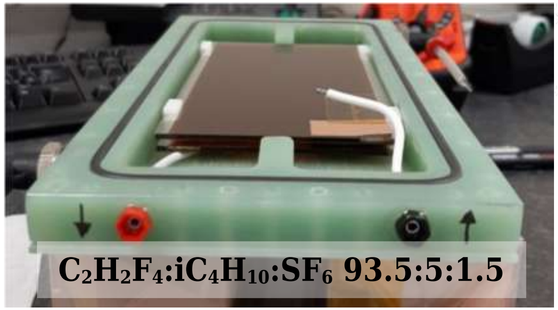


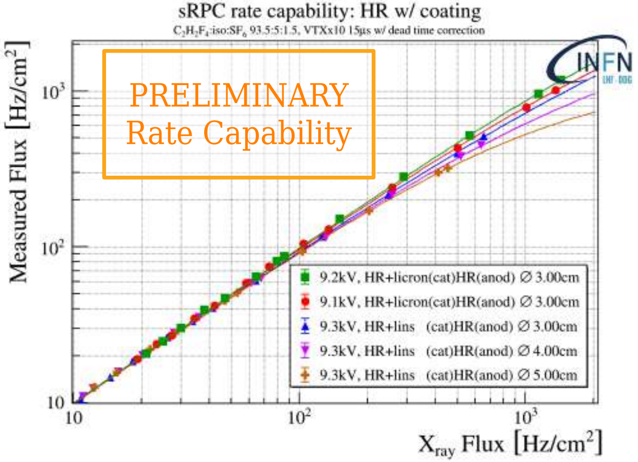
sRPC – an MPGD-tech based RPC

Glass 140×78 mm²
DLC 120×64 mm²

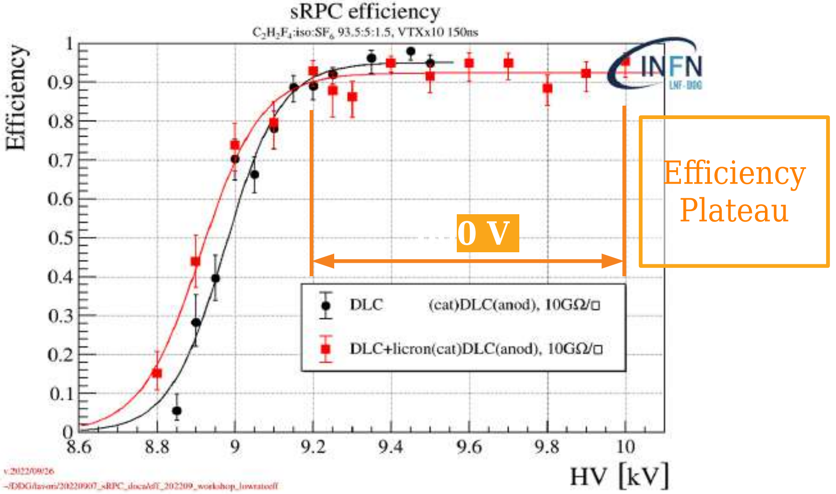
DLC-based RPC:

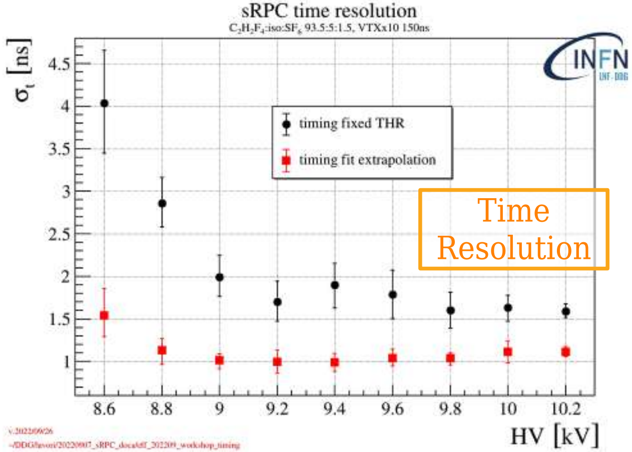
- **From bulk resistivity to surface resistivity**: easy tunable resistivity w.r.t. bakelite or glass
- µ-RWELL inspired **High Rate schemes**
- Flexible substrate





A promising novel technology, from MPGD material and technology experience.





WP7.3.2 – Summary

The activity of WP7.3.2 task proceeds on **two parallel paths:**

1) The **industrialization** of a part of the construction steps of the µ-RWELLs at the **ELTOS** company (Arezzo – IT), in close **collaboration** with the **CERN-EP-DT-MPT** Workshop:
   - Advances in the TT; **more contruction steps** performed by ELTOS
   - Detector finalization (Kapton Etching, …) performed at CERN
2) The R&D with CERN on the various µ-RWELL layouts is focusing on different items:
   - Design/optimization of the PEP layout → **PEP-dot** (97% geom. acceptance)
   - Design of two **2D strip R/O** (capacitive sharing and top strip patterned)
   - Prototype gain characterization with X-ray @LNF-INFN
   - Beam Test in **June'23 in H8-SpS** for all the new prototypes.

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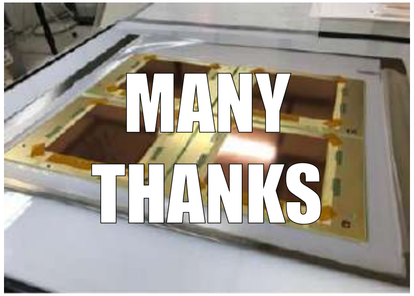


Spare

µ-RWELL technology spread

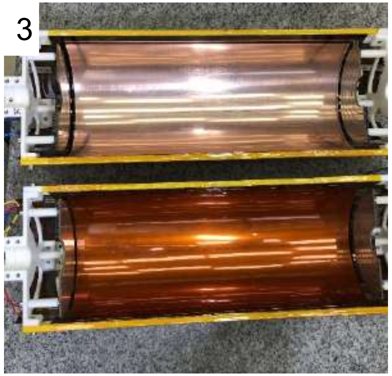
The µ-Resistive WELL is proposed in

1. **CLAS12 @ JLAB:** the upgrade of the muon spectrometer
2. **X17 @ n_TOF EAR2**: for the amplification stage of a TPC dedicated to the detection of the X17 boson
3. **TACTIC @ YORK Univ.:** radial TPC for detection of nuclear reactions with astrophysical significnace
4. **Muon collider:** hadron calorimeter
5. **CMD3:** uRWELL Disk for the upgrade of the tracking system
6. **URANIA-V**: a project funded by INFN-CSN5 for neutron detection,
7. **UKRI:** neutron detection with pressurized ^{3}He-based gas mixtures

1

2

3



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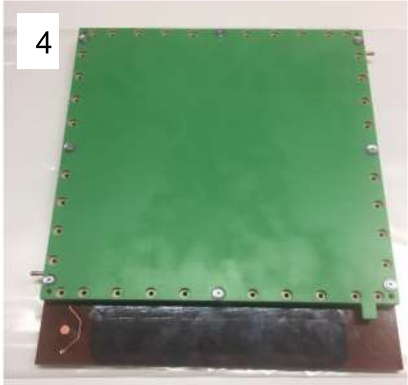

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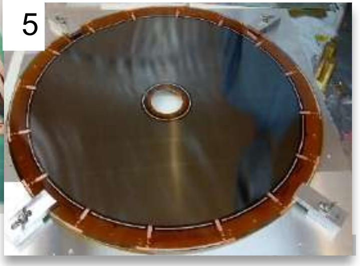

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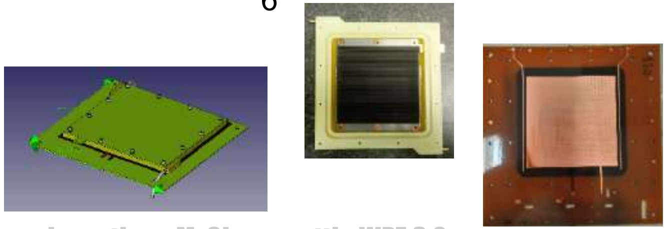

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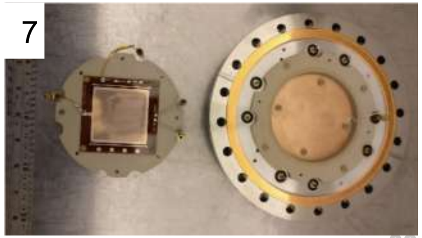
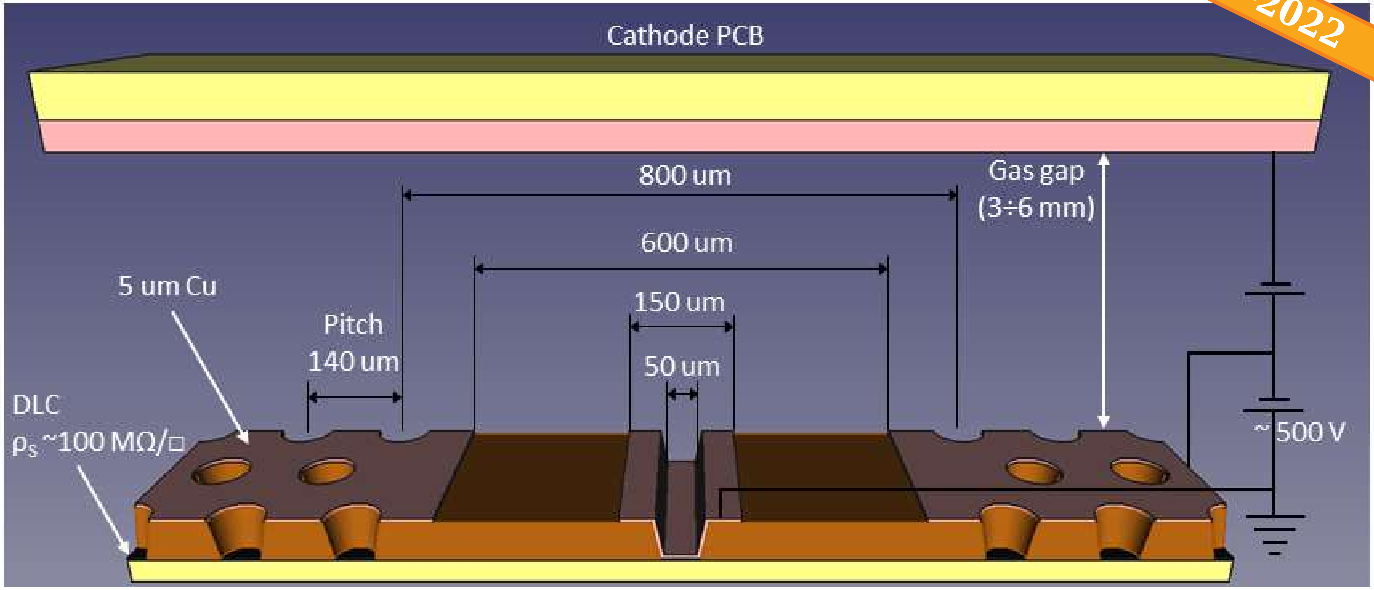


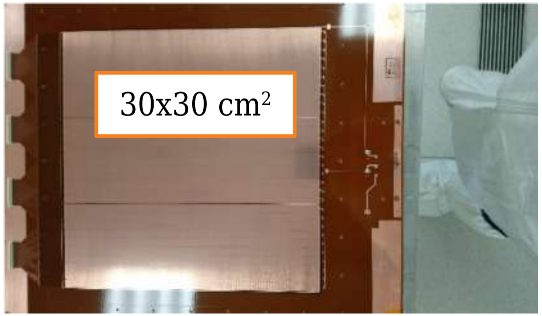
The PEP High Rate layout

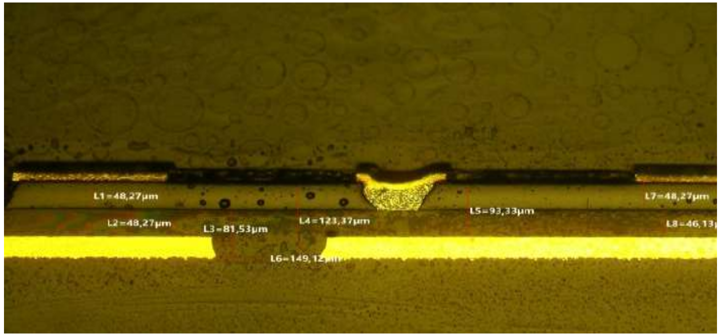
2021-2022



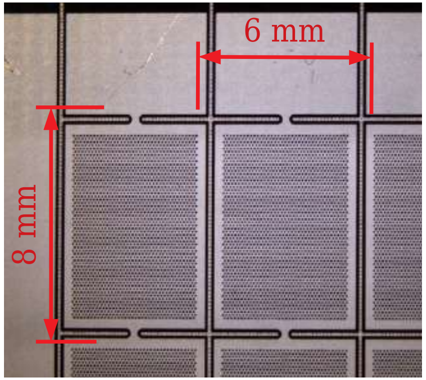
PEP: Patterning – Etching – Plating

- **Grounding from top** by kapton etching and plating
- **Scalable to large size**



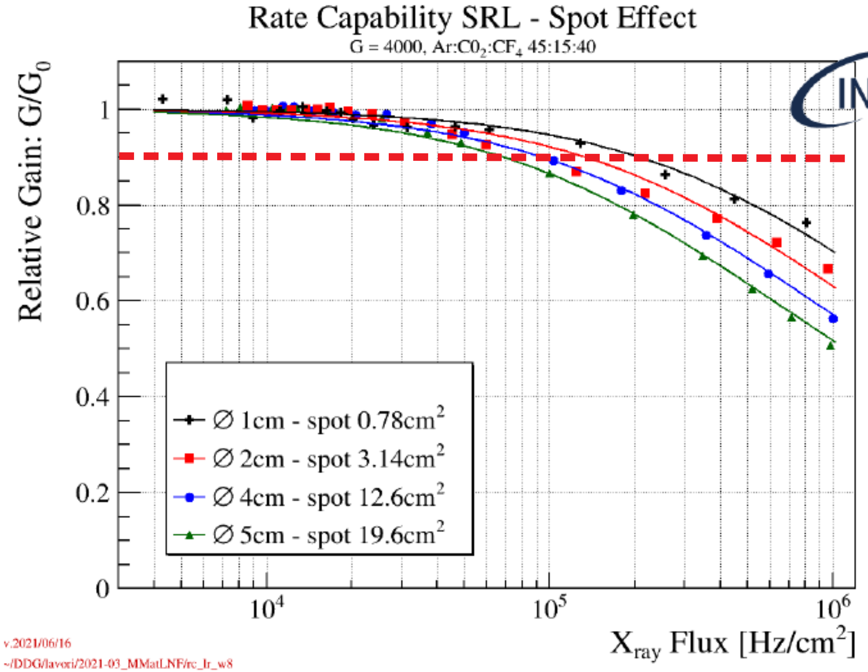


Unitary cell.
black - the exposed kapton is visible.

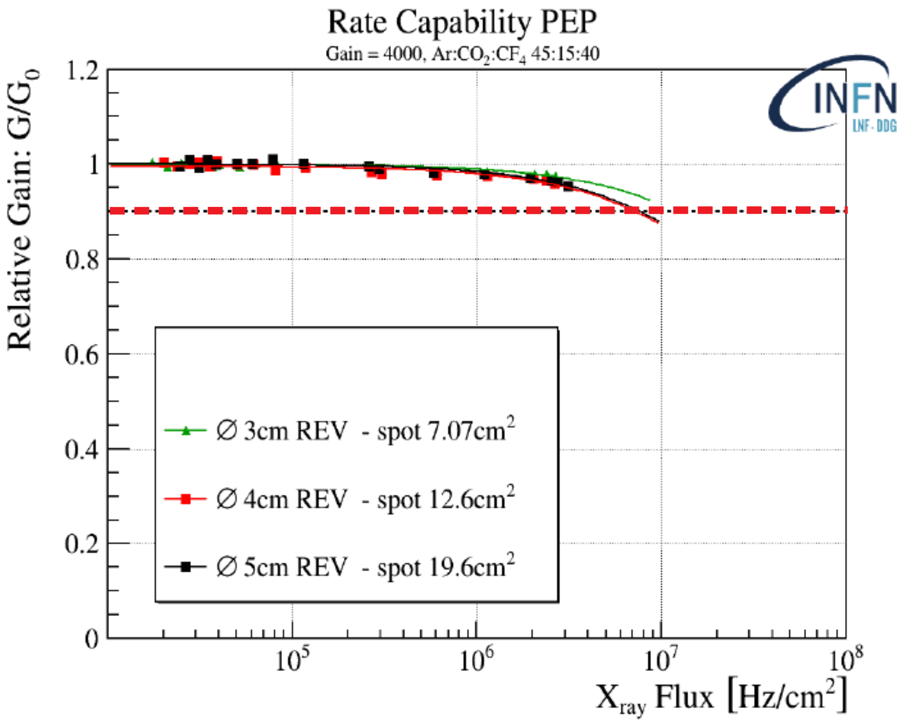


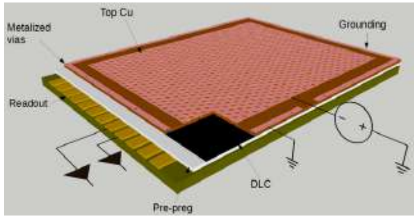
Rate capability – X-Ray measurements

Low Rate



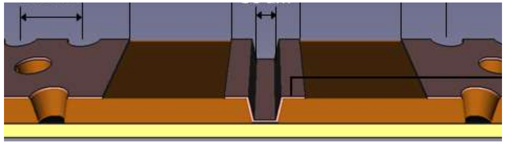
High Rate



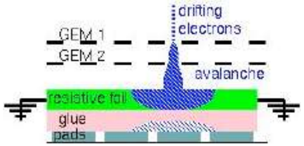


Rate capability compatible with m.i.p. as measured @PSI O(10MHz).

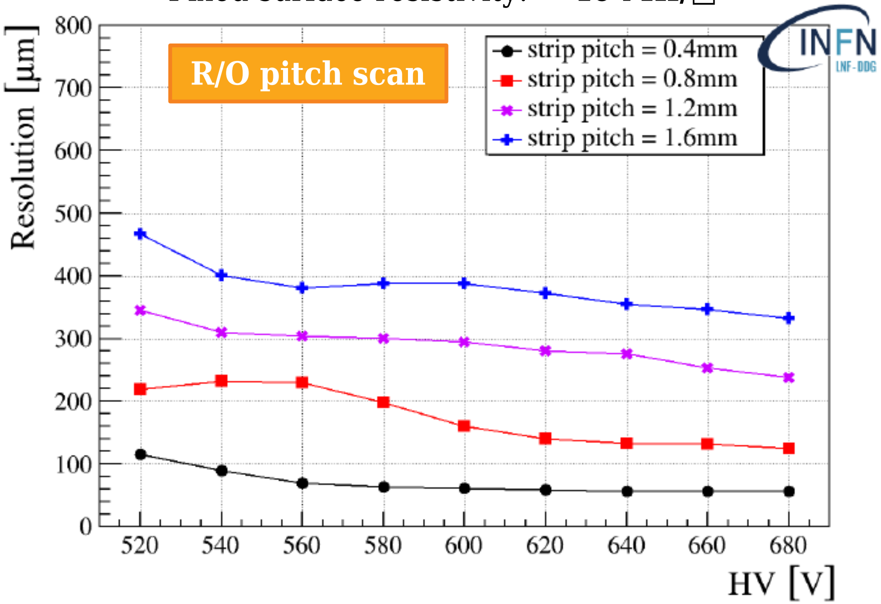
Different primary ionization ⇒ Rate Cap $_{\text{m.i.p.}}$ = 3×Rate Cap $_{\text{X-ray}}$

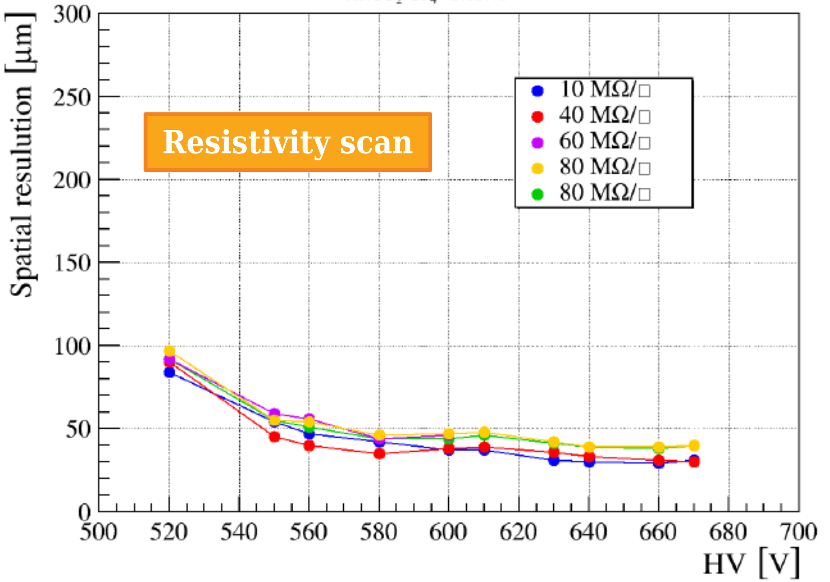


μ-RWELL: DLC charge spread



Fixed surface resistivity: **~ 40 MΩ/□**





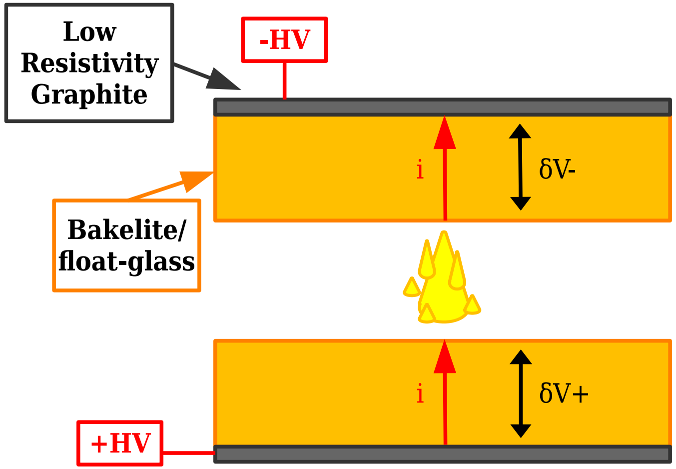
Fixed strip pitch (0.4 mm) and width (0.15 mm)

Need to **reduce** # FEE **channels**
=
Increase the R/O **pitch**

As expected: reduction of the space resolution.

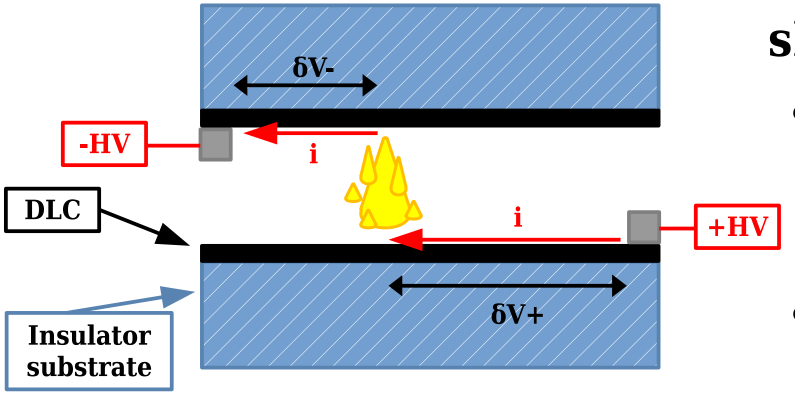
No effects in **this resistivity range**.
→ DLC resistivity uniformity is not a crucial parameter
Near future: charge dispersion through different R/O architecture → capacitive sharing R/O

Bulk RPC vs Surface RPC



Classical RPCs

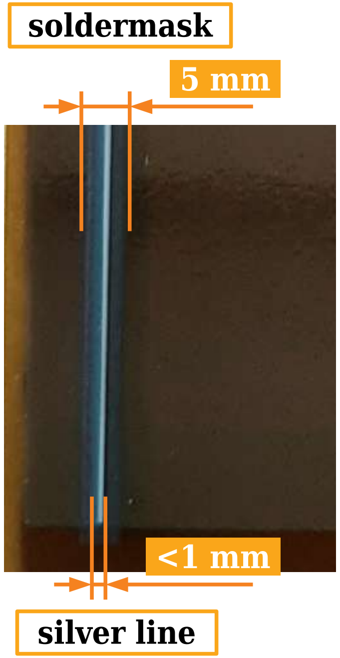
- Bulk resistivity electrodes (bakelite, float-glass, …)
- Recovery time proportional to **volume resistivity, electrode thickness**
  - $\tau=\rho_V\varepsilon_0(\varepsilon_r+2d/g)$
  - Low volume resistivity and thin electrodes, together with the reduction of the gas gain (⊕high gain low noise pre-amp) is the standard recipe to increase the detector rate capability.

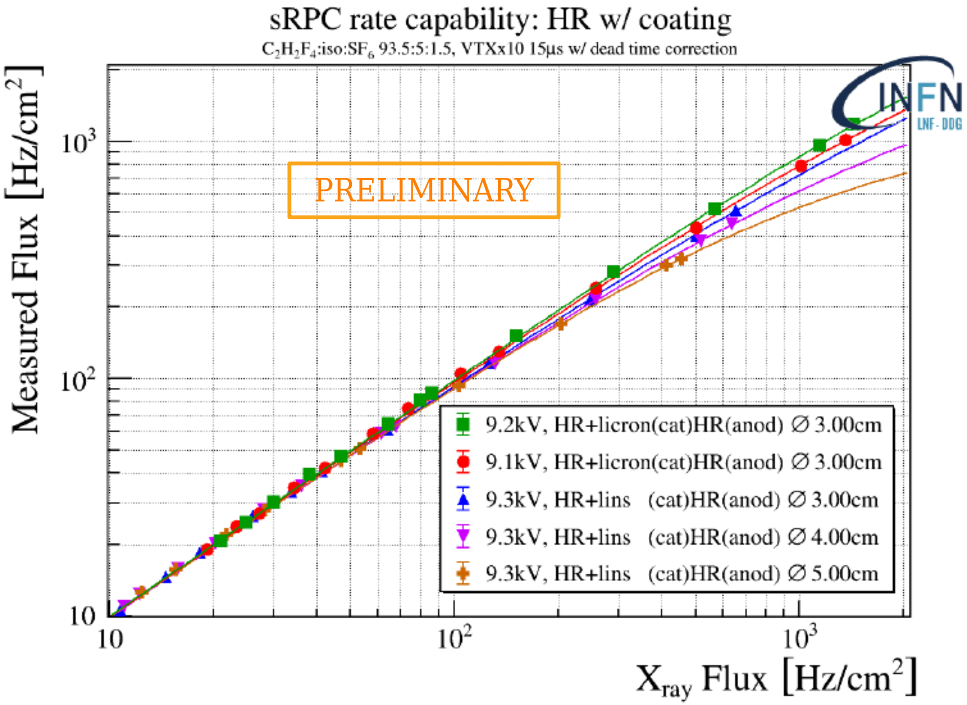


sRPCs - surface RPC

- Surface resistivity electrodes manufactured with sputtering techniques of Diamond-like-carbon (DLC) on flexible supports
  - The technology allows to realise large electrodes with a DLC **surface resistivity** in a **very wide range: 10 MΩ/□ ÷ 10 GΩ/□**
- High density current evacuation schemes, similar to those used for resistive MPGD (μ-RWELL and MicroMegas), can be implemented to improve the rate capability of the detector

High Rate layout – preliminary results





A **preliminary** measurement of the **rate capability** (defined as the radiation flux corresponding to an efficiency drop of 20%) of the high-rate layout has been **performed** by irradiating the detector **with a 5.9 keV X-ray gun** with a spot size comparable with the pitch of the conductive grid realized on the DLC ($\rho_{DLC}\approx1.6$ GΩ/□).

Rate capability of ~1 kHz/cm² with X-ray